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Attorney Docket No. 015290-458

Patent

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Patent of

Christopher C. Chang et al.

Patent No.: 6,805,952 B2

Issued: October 19, 2004

Title: LOW CONTAMINATION PLASMA CHAMBER COMPONENTS AND METHODS FOR MAKING THE SAME

REQUEST FOR CERTIFICATE OF CORRECTION

Commissioner for Patents  
P.O. Box 1450  
Alexandria, VA 22313-1450

Certificate  
NOV 23 2004  
of Correction

Sir:

Issuance of a Certificate of Correction for the above-captioned patent is respectfully requested in accordance with the accompanying Form PTO-1050 (submitted in duplicate).

- ☐ The requisite Government fee of \$100.00 (1811)
- ☐ Is submitted herewith.
- ☐ Is authorized to be charged to Deposit Account No. 02-4800.
- ☐ Charge \_\_\_\_\_ to credit card. Form PTO-2038 is attached.
- ☒ It is believed that payment of a fee is unnecessary.

Column 10, line 16, Claim 16 is incomplete as noted on the attached Form 1050.

The Director is hereby authorized to charge any appropriate fees under 37 C.F.R. § 1.20(a) that may be required by this paper, and to credit any overpayment, to Deposit Account No. 02-4800. This paper is submitted in duplicate.

Respectfully submitted,

BURNS, DOANE, SWECKER & MATHIS, L.L.P.

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By

  
Peter K. Skiff

Registration No. 31,917

Date: November 19, 2004



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DATED : October 19, 2004  
INVENTOR(S) : Christopher C. Chang et al.

It is certified that error appears in the above-identified patent and that said Letters Patent is hereby corrected as shown below:

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In column 10, line 16 of the patent, "16. The component of claim 15, wherein the coating is." should read as follows:

--16. A component of a plasma etch reactor, the component comprising aluminum having an anodized or non-anodized plasma exposed surface, the component comprising an as-sprayed plasma sprayed coating on a plasma exposed surface of the component, the coating being a ceramic material selected from the group consisting of alumina, yttria, zirconia, silicon carbide, silicon nitride, boron carbide and boron nitride, and the coating having an as-sprayed surface roughness that promotes the adhesion of polymer deposits formed during etching of semiconductor substrates in the plasma etch reactor.--

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PATENT NO. 6,805,952

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